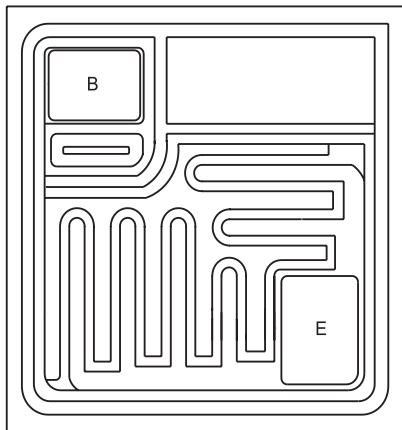


PROCESS DETAILS

Process	EPITAXIAL PLANAR
Die Size	27 x 27 MILS
Die Thickness	9.0 MILS
Base Bonding Pad Area	5.3 x 3.8 MILS
Emitter Bonding Pad Area	5.3 x 6.5 MILS
Top Side Metalization	Al - 30,000Å
Back Side Metalization	Au - 18,000Å

GEOMETRY



BACKSIDE COLLECTOR

R1

GROSS DIE PER 4 INCH WAFER

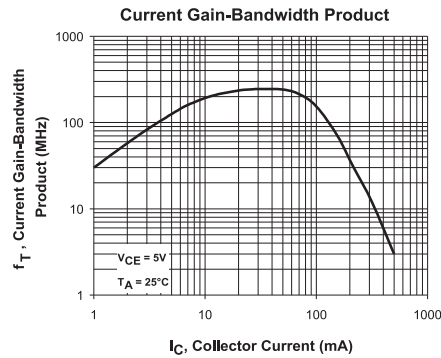
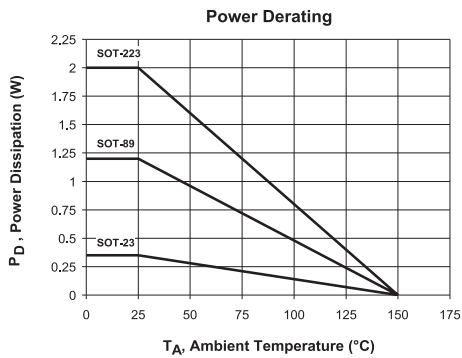
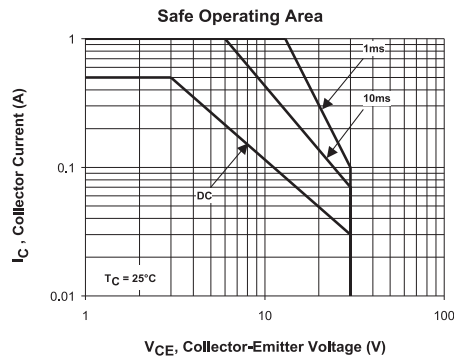
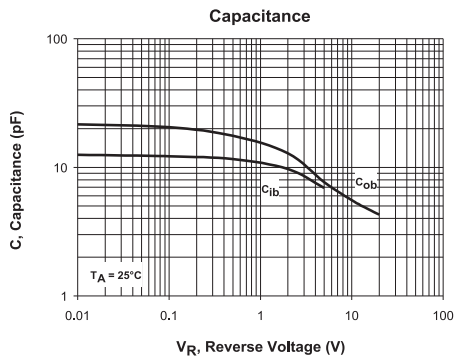
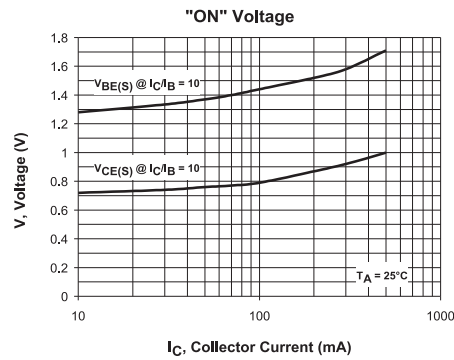
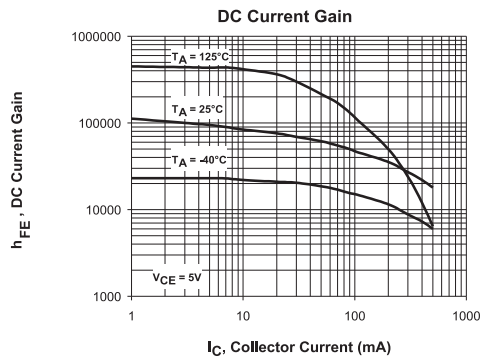
15,440

PRINCIPAL DEVICE TYPES

CMPTA63
CMPTA64
CXTA64
CZTA64
MPSA63
MPSA64

145 Adams Avenue
Hauppauge, NY 11788 USA
Tel: (631) 435-1110
Fax: (631) 435-1824
www.centrasemi.com

R3 (1-August 2002)



145 Adams Avenue
Hauppauge, NY 11788 USA
Tel: (631) 435-1110
Fax: (631) 435-1824
www.centrasemi.com

R3 (1-August 2002)